

A marked up version showing amendments to any claims being changed is provided in one or more accompanying pages separate from this amendment in accordance with 37 C.F.R. § 1.121(c)(1)(ii). Any claim not accompanied by a marked up version has not been changed relative to the immediate prior version, except that marked up versions are not being supplied for any added claim or canceled claim.

## CLAIMS

Cancel Claims 4-44.

1 2. (Once Amended) A sputtering target according to claim 1 comprising one or more of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag, and Pt.

2 45. (New) The sputtering target of claim 1 comprising an alloy which includes at least one of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag and Pt.

46. (New) The sputtering target of claim 1 comprising Al.

47. (New) The sputtering target of claim 1 comprising Ti.

48. (New) The sputtering target of claim 1 comprising Cu.

49. (New) The sputtering target of claim 1 comprising Ta.

50. (New) The sputtering target of claim 1 comprising Ni.

51. (New) The sputtering target of claim 1 comprising Mo.
52. (New) The sputtering target of claim 1 comprising Au.
53. (New) The sputtering target of claim 1 comprising Ag.
54. (New) The sputtering target of claim 1 comprising Pt.
55. (New) A sputtering target formed from a cast material and comprising:  
a substantial absence of pores, voids and inclusions; and  
an average grain size of less than about 1  $\mu\text{m}$ .
56. (New) The sputtering target of claim 55 comprising one or more of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag, and Pt.
57. (New) The sputtering target of claim 55 comprising an alloy which includes at least one of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag and Pt.
58. (New) The sputtering target of claim 55 further comprising a substantial absence of precipitates.
59. (New) The sputtering target of claim 55 further comprising a substantially uniform structure and texture at any location.

60. (New) The sputtering target of claim 55 further comprising a substantially homogeneous composition at any location.

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